

PATENT

Atty. Docket No.: 006915 USA P02/FEP/P3I/PJT  
RW Ref. No.: APM/001-02-CP1-2

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of: )  
Kenneth COLLINS, et al. ) Group Art Unit: 2893  
)  
Entitled: PLASMA IMMERSION ION )  
IMPLANTATION PROCESS USING A PLASMA )  
SOURCE HAVING LOW DISSOCIATION ) Examiner: Jack S. Chen  
AND LOW MINIMUM PLASMA VOLTAGE )  
)  
Serial No.: 10/646,533 )  
)  
Filing Date: August 22, 2003 )

INFORMATION DISCLOSURE STATEMENT UNDER 37 CFR 1.97(c)

Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

Sir:

In accordance with 37 CFR 1.56, the references listed below and on the attached form PTO-1449 are being brought to the attention of the Examiner for consideration in connection with the examination of the above-identified patent application. A copy of each foreign patent document and/or non-patent literature is enclosed.

This information is being submitted subsequent to the later of three months after the filing date of the present application or the mailing of the first Office Action on the merits, but before the mailing of a final action or the notice of allowance. Please

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see the attached USPTO Fee Transmittal for fee payment.

It is respectfully requested that the Examiner indicate consideration of the cited references by returning a copy of the attached form PTO-1449 with initials or other appropriate marks.

Respectfully submitted,



Dated: 6/17/2009

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